O find the conductivity and resistivity of an internsic semiconductor at temperature of 300°K. It is given that $n_i = 2.5 \times 10^{13}/\text{cm}^3$ Mn = 3800 cm²/V-s

Mp = 1800 cm²/V-s

9 = 1.6 × 10-19 C

5014 0; = n; e (Me + Mn) = 2.5 × 10¹³ × 1.6 × 10⁻¹⁹ (3,8 50 + 18 00) = 0.0224 S/cm.

Pi = 1 = 1 = 44.64

germanium at 300° k is 0.47.52-m.

The electron mobility at 300° k
in germanium is 0.39 m 24/5.

The hole mobility un at 300° k
in germanium is 0.19 m²/v.s.

The ded Calculate the density
of electrons in the intrinsic
material. Also calculate the
drift velocity of holes and
electrons for an electric field
(E=107. V/m).

intrinsic resistivity (Pi) = 0.47 R-m intrinsic conductivity (0;) = p = 1 = 2-12766 S/m Me = 0.39 m2/V-s Mn = 0.19 m2/Vs e= 1.6 ×10-19 C O; = hie (Met Mh) no= Of e(Me+Mn) = 2.12766 1.6×1519(0.39.40.19) n= = 2.293×109/m3/ Ans E= 104 V/m Vn= MeE = 0.39×104 In = 3900 m/s Ans

2h = Mh = -0.19 × 10 9 Nh = 1900 m/s ANS

(3) The intrinsic carrier Concentra-- thion for silicon at roomtemp. is 1.5 × 10 /cm3. If the mob. - ility of electrons and holes are 1300 cm2/v-s and 450 cm2/vs respectively. what is the condu-- ctivity of silicom (intrinsic) at 300 kg by silicon is doped with 1016 boron atoms per ec, what is its conductivity. == n== 1.5 x10 /cm3 Mh = 450 cm2/V-s

Me = 1300 cm2/V-s Of= nie (He+Uh) = 1.5 x10 x1.6 x10 19 (1300 + 450) 0; = 4.2 ×10-6 S/cm.) ANS.

After Dobing NA = 1018/cm3

Op = NAC Mh = 1018 X1.6 X1019 X 450 Op = 72 S/cm Ans.

(4) Find the conductivity of intrinsic germanium at 300°K. If donor type impurity is added to the extent of 1 impurity atom in 107 germanium atoms, find the conductivity. Given that

Mi= 2.5 × 10 13/cm3 Mh = 1800 cmy V-S Me = 3800 cm2/v-s Concentration of Ge atoms = 4.41 X1022/cit = 2.5×10×1.6×1519 (3800+1800) σρ = 0.0224 S/cm ANS. MNO. of ghe atoms/cm3=4.41×102/cm3 ND = 4.41×1022 - 4.41×10 5/2m3 M2ND= 4.41×1015/cm3

Concentration of electrons. $p = \frac{n_0^2}{ND} = \frac{(2.5 \times 16^3)^2}{4.41 \times 1615}$ P= 1.417×1011/cm3

OE= enome = 1.6x10 9x 4.41x10 5 3800 OE = 2-68 S/cm/ ANS

A pd (Potential difference) of 10V is applied longitudinally to a rectangular specimen of intrinsic Ge of langth 25 mm, width 4 mm and thickness 1-5 mm. Determine at roomtenp. 1) electron and have drift velocities. (11) the conductivity of intrinsic germanium if intrinsse corrier mily is 2-5×1019/m3 (111) Total current.

My Giren! He= 0.38 x 70 2/vs, 4n= 0.18 m/ks 1) 6= 1/e = 10.025 = 400 V/m. Uc = He KE = 0.38 X400 De= 152 m/s/ DONS Un = 41 XE = 0.18 × 400 1 Un= 72 m/s/ Ans (il) O:= hie (Met lun) = 2-5×10 4×1.6×1519(0.38+0.18) OF = 2.24.5/m/ ANS

(iii) J = 0; Ea = 2.24 × 450 × 4×153 × 1.5×153 T = 5.376 mA) Ans

Tutorial - I

1) In a certain copper conductor, the current density is 2.4 A/mm² and electron density is 5 x 1028 free electrons per m3 of the copper. Determine the drift velocity of the electrons.

J=2.4 A/mm2 = 2.4 × 106 A/m2

(dorgeon electron) q = 1.6 × 10 19 C

J = @n 918 $9 = \frac{J}{nq} = \frac{2.4 \times 10^6}{1.6 \times 10^{-19} \times 5 \times 10^{28}}$

(2) A conductor material has a free electron density of 1024 electrons per m3. When a valtage is applied, a constant drift relocity of 1.5 ×10-2 m/s is attained by the electron. If the cross-sectional area of the mortenal is 1 em² calculate the magnitude of current. There

9 = 1.6×10-19 C.

U = 1.5 × 15-2 m/s = 0.015 m/s] J=0

 $a = 1 \text{ cm}^2 = 1 \times 10^{-4} \text{ m}^2$

9nva = 1.6×10-19×1024×0.015×1×10-4 magnitude of (I) =

= 0.24 A ANS

J= ngv= nev

T= heva/

NguE

3. A specimen of germanium at 300 k for which the density of carriers is 2.5 x 1013 per cm3, is doped with impurity atoms such that there is one impurity atom for 10 germanium atoms. All the impurity atoms may be assumed ionized. The conductivity of doped material is 25.64 5/2m. Carrier mobility for germanium at 300 k is 3600 cm/v.s. Carrier mobility for germanium at 300 k is 3600 cm/v.s. have doped material, find the electron and have density.

501 $\sigma = 25.64 \frac{5}{69} \frac{5}{10^{-19}} c$

charge on electron (9) = 1.602 × 10-19 c.
mobility Me= 3600 cm²/V-s

On = ng/Me = ND q/Me - D

ND = 0n = 25.64 1.602 × 1019 × 3600

= 4.45 ×1016/cm3

(i) Concentration of electron n2 ND = 4.45 X10 1/cms

(ii) Concentration of hole, P = not = (2.5 ×1013)2.

= 1.4 × 1010 / cm3

Ans

4) A donor type impurity is added to the extent of 1 atom per 106 atoms of an intrinsic semiconductor (Silicon). Calculate (1) Resulting donor atom concentration (ii) Resulting mobile electron concentration (iii) Resulting hole concentration. (iv) conductivity of doped silicon sample. (V) If silicon bar is 0.5 cm long, cross-section area of (50×10-4) cm2. Find its resistivity. Concertation of silicon atoms = 5×1022 cm-3 Soly $N_{D} = (no. g silicon atom km3) \times (donor impurity)$ = 5 × 10²² × 106 = 5 × 16 16 / cm3 ANS (ii) Mobile electron concentration $n \simeq N_D = 5 \times 10^{16} / cm^3$ ANS.

(iii) Hole concentration $p = \frac{h^2}{N_D} = \frac{(1.45 \times 10^{10})^2}{5 \times 10^{16}} = 4.205 \times 10^3$ per cm³ ANS. (IV) Conductivity of doped vilicon 0=ng/le=5x10x1.602x1519x1300 =10.413 5/Em (v) Revistivity \$ p= == = = = 0.096 \ \(\omega \cdot \omega \omega \cdot \omega \c Resistance y given semiconductor

 $R = \frac{Pl}{a} = \frac{0.096 \times 0.5}{(50 \times 10^{5})^{2}} = 1920.92$ ANS